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Enhanced conductivity in pulsed laser deposited Ce$_{0.9}$Gd$_{0.1}$O$_{2-\delta}$/SrTiO$_3$ heterostructures

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Significant enhancement in the electrical conductivity of Ce$_{0.9}$Gd$_{0.1}$O$_{2-\delta}$ (CGO) thin films (250 and 500 nm) deposited on MgO(001) substrate is observed by introducing ~50 nm thick SrTiO$_3$ buffer layer film. Introduction of the buffer layer is found to form epitaxial films, leading to minimal grain boundary network that results in a free conduction path with near-zero blocking effects perpendicular to current flow. The in-plane conductivity measurements confirm increase in conductivity with increase in compressive strain on CGO films. © 2010 American Institute of Physics. [doi:10.1063/1.3497294]

Gadolinium doped ceria is a well-known oxygen ionic conductor for applications such as solid oxide fuel cells (SOFCs), gas sensors, and gas separation membranes.\textsuperscript{1–3} Ce$_{0.9}$Gd$_{0.1}$O$_{2-\delta}$ (CGO) exhibit larger ionic conductivity than yttrium stabilized zirconia, the conventional fuel cell electrolyte.\textsuperscript{4,5} There is a huge interest to obtain ionic thin films with less Ohmic resistance, scaling linearly with thickness, thus operating at lower temperature.\textsuperscript{6} CGO deposited on substrates like MgO(001), LaAlO$_3$(001), NdGaO$_3$(001), SrTiO$_3$(001), and SrTiO$_3$(001) results in polycrystalline or epitaxial thin film.\textsuperscript{7–13} From the view point of electrical transport, CGO is pure ionic conductor and the substrate contribution to large lattice misfit between substrate and film results in polycrystalline or epitaxial thin films.\textsuperscript{14} However, CGO thin films on MgO(001) are polycrystalline due to large lattice mismatch between substrate and film ($a_{\text{CGO}}-a_{\text{Mgo}}/a_{\text{CGO}} \times 100 = 9.1\%$) resulting in blocking effects due to the large density of grain boundary network.\textsuperscript{15,16} The lattice mismatch between SrTiO$_3$ (STO) and CGO reduces to ~1.9\% ($a_{\text{CGO}}-a_{\text{STO}}/a_{\text{STO}} \times 100 = 1.9\%$) by 45° in-plane rotation of CGO with respect to STO resulting in epitaxial films.\textsuperscript{10} The major difficulty in thin film conductivity measurements is to separate the contribution of the substrate from the total measured resistance and evaluate the film conductivity. However, polycrystalline STO shows electronic conductivity only above 300 °C in reducing conditions, and Sanna et al.\textsuperscript{10} have shown that for 20% molar samaria doped ceria (SDC) deposited on STO buffer-layer-MgO (SDC/STO/MgO) the electronic conductivity of STO is negligible for high p$_{O_2}$ values. In this work, conductivity of CGO films with different thickness (250 and 500 nm) were deposited on MgO(001) and MgO(001)/STO$_{50 \text{ nm}}$ measured in air, where CGO is pure ionic conductor and the substrate contribution [MgO(001) and MgO(001)/STO$_{50 \text{ nm}}$] is negligible. STO buffer layer (lattice parameter $a=b=c=3.907$ Å) was deposited as 50 nm thick film on MgO in order to ensure epitaxial growth of CGO ($a=b=c=5.418$ Å) on MgO(001) ($a=b=c=4.219$ Å) substrate. Similar approach was successful in obtaining epitaxial superconducting YBa$_2$Cu$_3$O$_{7-\delta}$ (YBCO) thin films on MgO (001) and chemical and thermally stable Ce$_{0.9}$Sm$_{0.1}$O$_{2-\delta}$ on MgO.\textsuperscript{10,17,18}

CGO target was prepared from commercial powder (Rhodia, Purity 99.99%) by 120 MPa uniaxial pressure followed by sintering at 1500 °C for 24 h. Pulsed laser deposition using KrF laser (248 nm) was used to deposit STO (50 nm) and CGO (250 and 500 nm) thin films on MgO(001) substrate. STO films were deposited at oxygen partial pressure $P_{O_2}$ of 0.1 mbar, maintaining substrate temperature at 760 °C, and frequency of 2 Hz. After the deposition the STO film was cooled to room temperature at 10 °C per min rate in 1 mbar $P_{O_2}$. Similarly, CGO films were deposited at $P_{O_2}$ of 10$^{-2}$ mbar, substrate temperature of 750 °C, and frequency of 10 Hz with a cooling rate of 10 °C per min. Growth rate was 0.8 nm/min (2 Hz) and 4 nm/min (10 Hz) for the STO and CGO thin films respectively. The electrical properties were studied by both AC impedance and two-probe dc techniques in the temperature range 450–900 °C in air using gold (Au) current collectors onto La$_{0.7}$Sr$_{0.3}$MnO$_{3-\delta}$ (LSM) electrodes deposited onto the GCO film surface. LSM electrodes have high electronic conductivity and thermal expansion and ensure perfect adherence and full coverage of CGO at all temperatures. Au current collectors were deposited on LSM and annealed at 1000 °C for 12 h prior to the measurements for good contact formation. The impedance spectra were correlated with dc measurements to monitor electrode contribution.

Figures 1(a) and 1(b) show x-ray diffraction (XRD) patterns from representative MgO(001)/STO$_{50 \text{ nm}}$ and MgO(001)/STO$_{50 \text{ nm}}$/CGO$_{250/500 \text{ nm}}$ films. These reveal the cubic fluorite structure of CGO films deposited on MgO(001)/STO$_{50 \text{ nm}}$ with no evidence of secondary phases. Only (h00) diffraction peaks was detected indicating that the epitaxially grown STO$_{50 \text{ nm}}$ film with [100] direction perpendicular to substrate surface [Fig. 1(b)].

The lattice constant ($a$) of STO film is 3.924 Å, slightly larger than that in bulk STO (3.907 ± 0.001 Å), showing that the STO$_{50 \text{ nm}}$ film is in-plane compressed. The relative strain ($s$) is estimated from the relation, $s= (a-a_{\text{bulk}})/a_{\text{bulk}}$, where $a_{\text{bulk}}$ is the lattice constant of bulk. STO$_{50 \text{ nm}}$ film exhibited 0.45% strain leading to misfit of 2.3% between STO$_{50 \text{ nm}}$ buffer layer and CGO film. Similarly CGO$_{250 \text{ nm}}$ and

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CGO_{500} nm films deposited on MgO/STO_{50 nm} resulted in 0.12% and 0.09% strain in CGO lattice. These small values of strain indicate higher structural coherence in CGO films deposited on STO_{50 nm} buffer layer. However, the FWHM of strain indicates higher structural coherence in CGO films deposited on MgO substrate (3.49°) is one order larger than for the films deposited on MgO using a STO buffer layer (0.21°) [Figs. 1(c) and 1(d)]. This observation clearly demonstrates that STO_{50 nm} buffer layer improves the lattice match between MgO and CGO by inducing strain on CGO (0.12% and 0.09%) film. No strain is observed in polycrystalline CGO films deposited on MgO(001) under the same conditions.

The Φ scan on (311) peak of STO in MgO(001)/STO_{50 nm} films show four distinct peaks with same intensity and nearly 90° spacing between peaks (Fig. 2). Similar trend was observed for CGO(311) reflection, with a displacement of 45° with respect to MgO(311). Epitaxial growth of CGO(001) on MgO(001) with STO_{50 nm} buffer layer has been achieved through rotation of CGO lattice by 45° with respect to STO lattice. This clearly indicates that epitaxial CGO films were realized on STO_{50 nm} basal plane (5.54 Å) due to low misfit compared to MgO(001). The XRD patterns of MgO/STO_{50 nm}/CGO_{250 nm} heterostructures taken after electrical transport measurements at high temperature showed that the films retained their crystalline quality and, most important, the CGO is perfectly coherent with the STO, in agreement with XRD results, meaning that the CGO_{250 nm} layer grows rotated by 45° around the c axis and strains to match the STO basal plane. Increasing CGO thickness to 500 nm, it resulted in lowering of strain to 0.09%.

Figure 3(a) shows impedance spectra measured in air at 400 °C for MgO(001)/CGO_{250 nm}, MgO(001)/STO_{50 nm}/CGO_{250 nm}, and MgO(001)/STO_{50 nm}/CGO_{500 nm} films. The spectra consist of a single nonpressed semicircles and no electrode feature is apparent in the spectra because their low impedance contribution. A single RC element (i.e., a resistor in parallel with a capacitor) is used as equivalent circuit to obtain the impedance-frequency relation at various temperatures. A single impedance arc of the polycrystalline CGO thin films is ascribed to total contribution of the grains and grain boundaries to the ionic conductivity. The total resistance of the sample is measured as the diameter of the semicircle. Frequency distribution shows the RC relaxation times for the samples at 400 °C [Fig. 3(b)]. CGO films deposited on MgO(001)/STO_{50 nm} at 400 °C in air relax faster (10^{-7} s) compared to those deposited on MgO(001) substrate (10^{-6} s). The resistance measured by two probe dc method

![FIG. 1. (Color online) The θ-2θ scans of (a) MgO(001)/STO_{50 nm}, MgO(001)/STO_{50 nm}/CGO_{250 nm} and (b) MgO(001)/STO_{50 nm}/CGO_{500 nm}. Rocking curves of (002) reflection of CGO in (c) MgO(001)/STO_{50 nm}/CGO_{250 nm} and MgO(001)/STO_{50 nm}/CGO_{500 nm} and (d) MgO(001)/CGO_{250 nm}](https://apl.aip.org/doi/10.1063/1.3423015)

![FIG. 2. The Φ scan XRD patterns of MgO(001)/STO_{50 nm}/CGO_{250 nm} and MgO(001)/STO_{50 nm} heterostructures](https://apl.aip.org/doi/10.1063/1.3423015)

![FIG. 3. (Color online) (a) Nyquist plot and (b) frequency dependence of imaginary part impedance for measured in air at 400 °C for MgO(001)/CGO_{250 nm}, MgO(001)/STO_{50 nm}/CGO_{250 nm} and MgO(001)/STO_{50 nm}/CGO_{500 nm}. Inset is electrodes arrangement used for in-plane conductivity measurements](https://apl.aip.org/doi/10.1063/1.3423015)
is nearly equal to the value of resistance obtained from the impedance spectrum due to the low contribution of the electrodes polarization. No thermal hysteresis was observed in MgO(001)/CGO250 nm, MgO(001)/STO50 nm/CGO250 nm, and MgO(001)/STO50 nm/CGO500 nm heterostructures. The capacitance value obtained for heterostructures are \( \sim 10^{-11} \) F and is of the order of the stray capacitance i.e., C value might not be characteristic of CGO polycrystalline bulk material but it is typical of doped-ceria in thin film shape.\(^7\) Figure 4 shows Arrhenius plots of MgO(001)/CGO250 nm and MgO(001)/STO50 nm/CGO250 nm films measured in the temperature range of 450 to 900 °C in air. The activation energy (\( E_a \)) of MgO(001)/CGO250 nm was calculated to be \( \sim 0.81 \) and 0.82 eV from Nyquist plots [Fig. 4(a)] and dc two probe [Fig. 4(b)] measurements. The activation values are in the range of 0.8–0.9 eV as obtained for polycrystalline CGO films.\(^14,19,20\)

The slight increase in the dc measurements in the entire temperature range were attributed to the contribution of electrodes adherent to the CGO film surface. At 450 °C, CGO films deposited on MgO(001)/STO50 nm exhibit fivefold larger conductivity than in the films deposited on MgO(001) substrate. At 900 °C, total conductivity is found to be 3.7 \( \times 10^{-5} \) S/cm, 5.1 S/cm, and 12.1 S/cm for MgO(001)/CGO250 nm, MgO(001)/STO50 nm/CGO500 nm, and MgO(001)/STO50 nm/CGO250 nm samples, respectively. The conductivity curves shift upwards in films with STO50 nm buffer layer. The calculated activation energies for MgO(001)/STO50 nm/CGO500 nm films were 0.93 and 0.94 eV. These activation energies correspond to the values reported for bulk doped ceria.\(^21\)

For coherent epitaxial growth, the lattice mismatch between thin film and substrate is accommodated entirely by strain within the film. As the film grows thicker the total strain energy in the film increases rapidly. The relaxation of this strain field determines the final film crystallinity. Mostly, the strain field caused by the lattice mismatch will be relaxed by generating dislocations and local lattice distortions, distribution of which strongly influence the film crystallinity. Large regions of lattice distortions may result in a columnar or polycrystalline growth, degrading the film quality and thus reducing the conductivity.\(^9,22,23\) In our MgO(001)/STO50 nm/CGO250/500 nm heterostructures, the presence of uniformly strained regions lead to epitaxial nearly single crystal films. The increase in conductivity is attributed to negligible number of grain boundaries perpendicular to current flow. Conductivity enhancements open up exciting opportunities for oxide ionic conductors in technologies such as SOFCs.